

PATENT Attorney Docket No. 99154X204201

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Fang et al.

For:

Application No. 09/595,227

Filed: June 16, 2000

METHOD FOR POLISHING A

MEMORY OR RIGID DISK WITH A PHOSPHATE ION-CONTAINING

POLISHING SYSTEM

Art Unit: 3723

Examiner: H. Shakeri



Commissioner for Patents Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated February 15, 2002, please enter the following amendments and consider the following remarks.

**AMENDMENTS** 

IN THE CLAIMS:

Please cancel claims 24-34 without prejudice.

Replace the indicated claims with:

1. (Amended) A method for planarizing or polishing a surface of a memory or rigid disk comprising abrading at least a portion of the surface with a polishing system comprising (i) a polishing composition comprising water, an oxidizing agent, and about 0.04 M or higher phosphate ion or phosphonate ion, and (ii) abrasive material.

## REMARKS

## The Present Invention

The present invention relates to a method of planarizing or polishing the surface of a memory or rigid disk. Claims 1-23 are pending.

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